IEC 62047-46

Edition 1.0 2025-04

INTERNATIONAL STANDARD

Semiconductor devices – Micro-electromechanical devices –
Part 46: Silicon based MEMS fabrication technology – Measurement method of tensile strength of nanoscale thickness membrane

Currently in preview, click buy full version

IEC 62047-46:2025-04(en)

THIS PUBLICATION IS COPYRIGHT PROTECTED
Copyright © 2025 IEC, Geneva, Switzerland

All rights reserved. Unless otherwise specified, no part of this publication may be reproduced or utilized in any form or by any means, electronic or mechanical, including photocopying and microfilm, without permission in writing from either IEC or IEC's member National Committee in the country of the requester. If you have any questions about IEC copyright or have an enquiry about obtaining additional rights to this publication, please contact the address below or your local IEC member National Committee for further information.

IEC Secretariat
3, rue de Varembé
CH-1211 Geneva 20
Switzerland

Tel.: +41 22 919 02 11
info@iec.ch
www.iec.ch

About the IEC
The International Electrotechnical Commission (IEC) is the leading global organization that prepares and publishes International Standards for all electrical, electronic and related technologies.

About IEC publications
The technical content of IEC publications is kept under constant review by the IEC. Please make sure that you have the latest edition, a corrigendum or an amendment might have been published.

IEC publications search - webstore.iec.ch/advsearchform
The advanced search enables to find IEC publications by a variety of criteria (reference number, text, technical committee, …). It also gives information on projects, replaced and withdrawn publications.

IEC Just Published - webstore.iec.ch/justpublished
Stay up to date on all new IEC publications. Just Published details all new publications released. Available online and once a month by email.

IEC Customer Service Centre - webstore.iec.ch/csc
If you wish to give us your feedback on this publication or need further assistance, please contact the Customer Service Centre: sales@iec.ch.

IEC Products & Services Portal - products.iec.ch
Discover our powerful search engine and read freely all the publications previews, graphical symbols and the glossary. With a subscription you will always have access to up to date content tailored to your needs.

Electropedia - www.electropedia.org
The world's leading online dictionary on electrotechnology, containing more than 22 500 terminological entries in English and French, with equivalent terms in 25 additional languages. Also known as the International Electrotechnical Vocabulary (IEV) online.

IEC 62047-46

Edition 1.0 2025-04

INTERNATIONAL STANDARD

Semiconductor devices – Micro-electromechanical devices – Part 46: Silicon based MEMS fabrication technology – Measurement method of tensile strength of nanoscale thickness membrane

INTERNATIONAL ELECTROTECHNICAL COMMISSION

ICS 31.080.99

ISBN 978-2-8327-0350-2

Warning! Make sure that you obtained this publication from an authorized distributor.

® Registered trademark of the International Electrotechnical Commission

CONTENTS

FOREWORD ... 3
1 Scope ... 5
2 Normative references ... 5
3 Terms and definitions ... 5
4 Requirements ... 6
4.1 In-situ on-chip tester design requirements ... 6
4.2 In-situ on-chip tester fabrication requirements ... 9
4.3 Testing environment requirements ... 9
5 Testing method ... 9
5.1 General ... 9
5.2 Nanoscale thickness membrane tensile strength testing method operation process ... 9
5.3 Nanoscale thickness membrane tensile strength testing method operation requirements ... 10
5.4 Tensile strength in-situ on-chip tester size recommendations ... 11
5.5 Tensile testing method analysis process ... 11
6 Test report ... 11
Annex A (informative) Examples of tensile strength testing on nanoscale thickness membrane ... 12
A.1 General ... 12
A.2 Size recommendations of nanoscale thickness membrane tensile strength in-situ on-chip tester ... 12
A.3 Nanoscale thickness membrane tensile strength test ... 13
Bibliography ... 15

Figure 1 – In-situ on-chip tensile strength tester ... 8
Figure 2 – Nanoscale thickness membrane tensile strength testing method operation process ... 10
Figure A.1 – Design of the deflection ruler and the displacement ruler ... 13
Figure A.2 – Bulk silicon fabrication process example of in-situ on-chip tester ... 14
Figure A.3 – Test area ... 14

Table A.1 – Size recommendations of nanoscale thickness membrane tensile strength in-situ on-chip tester and corresponding c value ... 12
Table A.2 – Nanoscale thickness membrane tensile strength test results ... 14

currently in preview, click buy full version

INTERNATIONAL ELECTROTECHNICAL COMMISSION

SEMICONDUCTOR DEVICES – MICRO-ELECTROMECHANICAL DEVICES –

Part 46: Silicon based MEMS fabrication technology – Measurement method of tensile strength of nanoscale thickness membrane

FOREWORD

1) The International Electrotechnical Commission (IEC) is a worldwide organization for standardization comprising all national electrotechnical committees (IEC National Committees). The object of IEC is to promote international co-operation on all questions concerning standardization in the electrical and electronic fields. To this end and in addition to other activities, IEC publishes International Standards, Technical Specifications, Technical Reports, Publicly Available Specifications (PAS) and Guides (hereafter referred to as "IEC Publication(s)"). Their preparation is entrusted to technical committees; any IEC National Committee interested in the subject dealt with may participate in this preparatory work. International, governmental and non-governmental organizations liaising with the IEC also participate in this preparation. IEC collaborates closely with the International Organization for Standardization (ISO) in accordance with conditions determined by agreement between the two organizations.
2) The formal decisions or agreements of IEC on technical matters express, as nearly as possible, an international consensus of opinion on the relevant subjects since each technical committee has representation from all interested IEC National Committees.
3) IEC Publications have the form of recommendations for international use and are accepted by IEC National Committees in that sense. While all reasonable efforts are made to ensure that the technical content of IEC Publications is accurate, IEC cannot be held responsible for the way in which they are used or for any misinterpretation by any end user.
4) In order to promote international uniformity, IEC National Committees undertake to apply IEC Publications transparently to the maximum extent possible in their national and regional publications. Any divergence between any IEC Publication and the corresponding national or regional publication shall be clearly indicated in the latter.
5) IEC itself does not provide any attestation of conformity. Independent certification bodies provide conformity assessment services and, in some areas, access to IEC marks of conformity. IEC is not responsible for any services carried out by independent certification bodies.
6) All users should ensure that they have the latest edition of this publication.
7) No liability shall attach to IEC or its directors, employees, servants or agents including individual experts and members of its technical committees and IEC National Committees for any personal injury, property damage or other damage of any nature whatsoever, whether direct or indirect, or for costs (including legal fees) and expenses arising out of the publication, use of, or reliance upon, this IEC Publication or any other IEC Publications.
8) Attention is drawn to the Normative references cited in this publication. Use of the referenced publications is indispensable for the correct application of this publication.
9) IEC draws attention to the possibility that the implementation of this document may involve the use of (a) patent(s). IEC takes no position concerning the evidence, validity or applicability of any claimed patent rights in respect thereof. As of the date of publication of this document, IEC had not received notice of (a) patent(s), which may be required to implement this document. However, implementers are cautioned that this may not represent the latest information, which may be obtained from the patent database available at https://patents.iec.ch. IEC shall not be held responsible for identifying any or all such patent rights.

IEC 62047-46 has been prepared by subcommittee 47F: Micro electromechanical systems, of IEC technical committee 47: Semiconductor devices. It is an International Standard.

The text of this International Standard is based on the following documents:

Draft	Report on voting
47F/500/FDIS	47F/507/RVD

Full information on the voting for its approval can be found in the report on voting indicated in the above table.

currently in preview, click buy full version

The language used for the development of this International Standard is English.

This document was drafted in accordance with ISO/IEC Directives, Part 2, and developed in accordance with ISO/IEC Directives, Part 1 and ISO/IEC Directives, IEC Supplement, available at www.iec.ch/members_experts/refdocs. The main document types developed by IEC are described in greater detail at www.iec.ch/publications.

A list of all parts in the IEC 62047 series, published under the general title *Semiconductor devices – Micro-electromechanical devices*, can be found on the IEC website.

The committee has decided that the contents of this document will remain unchanged until the stability date indicated on the IEC website under webstore.iec.ch in the data related to the specific document. At this date, the document will be

- reconfirmed,
- withdrawn, or
- revised.

currently in preview, click buy full versi

SEMICONDUCTOR DEVICES – MICRO-ELECTROMECHANICAL DEVICES –

Part 46: Silicon based MEMS fabrication technology – Measurement method of tensile strength of nanoscale thickness membrane

1 Scope

This part of IEC 62047 specifies the requirements and testing method to measure the tensile strength of membrane with nanoscale thickness (length from 100 µm to 5 000 µm, width from 100 µm to 1 000 µm, thickness from 50 nm to 500 nm) which is fabricated by micromachining technology used in silicon-based micro-electromechanical system (MEMS).

This document is applicable to in-situ tensile strength measurement of nanoscale thickness membrane manufactured by microelectronics technology and related micromachining technology.

With the devices scaling, the tensile strength degradation induced by defects and contaminations, becomes severer. This document specifies an in-situ testing method of the tensile strength of membrane with nanoscale thickness based on a MEMS technique. This document does not need intricate instruments (such as scanning probe microscopy and nanoindenter) and special test specimens.

Since in-situ on-chip tester in this document and device are fabricated with the same process on the same wafer, this document can give some practical reference for the design part.

2 Normative references

There are no normative references in this document.

3 Terms and definitions

For the purposes of this document, the following terms and definitions apply.

ISO and IEC maintain terminology databases for use in standardization at the following addresses:

- IEC Electropedia: available at https://www.electropedia.org/
- ISO Online browsing platform: available at https://www.iso.org/obp

3.1
tensile strength
R_m
maximum force experienced by the testing structure during tensile test divided by the original cross-sectional area of the testing structure

Note 1 to entry: The quotient is called tensile strength.

currently in preview, click buy full versi